

AMENDMENTS TO THE CLAIMS

Claims 1-4 (Cancelled)

Claim 5 (Previously Presented) A positive-working chemical-amplification photoresist composition which consists essentially of, as a uniform solution in an organic solvent:

- (A) 100 parts by weight of a film-forming resinous compound having acid-dissociable solubility-reducing groups in the molecule and capable of being imparted with an increased solubility in an aqueous alkaline solution by interaction with an acid, which resinous compound is a copolymeric resin consisting of from 50 to 85% by moles of the monomeric units of hydroxystyrene, from 10 to 30% by moles of the monomeric units of styrene and from 2 to 20% by moles of the monomeric units of a tert-alkylacrylate or methacrylate;
- (B) from 1 to 20 parts by weight of an acid-generating compound which is an onium salt compound having a fluoroalkylsulfonate as the anionic constituent;
- (C) from 0.01 to 5 parts by weight of a phosphorus-containing oxo acid,
- (D) an amine selected from the group consisting of secondary amines and tertiary amines, in an amount sufficient to exhibit a quenching effect and
- (E) an organic solvent to dissolve components (A) to (D).

Claim 6 (Previously Presented) The positive-working chemical-amplification photoresist composition as claimed in claim 5 in which the phosphorus-containing oxo acid as the component (C) is selected from the group consisting of phosphoric acid, phosphorous acid, phosphonic acid, phosphinic acid, phenylphosphinic acid and phenylphosphonic acid.

Claim 7 (Previously Presented) The positive-working chemical-amplification photoresist composition as claimed in claim 5 in which the tert-alkyl acrylate or methacrylate is tert-butyl acrylate or methacrylate.

Claim 8 (Previously Presented) The positive-working chemical-amplification photoresist composition as claimed in claim 5 in which the amount of the phosphorus-containing oxo acid as the component (C) is in the range from 0.1 to 2.0 parts by weight per 100 parts by weight of the component (A).

Claim 9 (Previously Presented) The positive-working chemical-amplification photoresist composition according to claim 5 wherein the amine is triethylamine, tributylamine, dibutylamine or triethanolamine.

Claim 10 (New) A positive-working chemical-amplification photoresist composition which consists of, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a film-forming resinous compound having acid-dissociable solubility-reducing groups in the molecule and capable of being imparted with an increased solubility in an aqueous alkaline solution by interaction with an acid, which resinous compound is a copolymeric resin consisting of from 50 to 85% by moles of the monomeric units of hydroxystyrene, from 10 to 30% by moles of the monomeric units of styrene and from 2 to 20% by moles of the monomeric units of a tert-alkylacrylate or methacrylate;

(B) from 1 to 20 parts by weight of an acid-generating compound which is an onium salt compound having a fluoroalkylsulfonate as the anionic constituent;

(C) from 0.01 to 5 parts by weight of a phosphorus-containing oxo acid,

(D) an amine selected from the group consisting of secondary amines and tertiary amines, in an amount sufficient to exhibit a quenching effect and

(E) an organic solvent to dissolve components (A) to (D).